

IN THE CLAIMS

Please amend Claims 1 – 13 as follows:

1. *(Previously Presented)* A method of manufacturing nanowires from semiconductor material, comprising the steps of:

providing a patterned etching mask having openings on a surface of a substrate made of the semiconductor material, which openings have a substantially uniform pitch;

placing the substrate with the etching mask in a liquid etchant for the semiconductor material;

anodically etching so as to form substantially parallel pores with a pitch corresponding to the pitch of the openings in the etching mask at a current density such that the diameter of the pores becomes at least as great as the pitch of the pores, whereby nanowires are formed;

oxidizing a surface of the nanowires, whereupon said surface is removed by etching; and

removing the nanowires from the substrate by means of vibration,

wherein the anodic etching is carried out in a first time period and a second time period, which periods correspond to a first and a second region along the nanowires, such that etching takes place in the second period at a higher current density than in the first period so that the nanowires formed have a greater diameter in the first region than in the second region, with the result that the nanowires break off in the second region upon removal.

2. *(Previously Presented)* A method as claimed in claim 1, wherein the removal takes place in a bath wherein a dispersion of the nanowires is formed.

3. *(Previously Presented)* A method as claimed in claim 1, wherein the step of oxidation and removal of the surface of the nanowires is repeated a number of times.

4. *(Previously Presented)* A method as claimed in claim 1, wherein the anodic etching is carried out during a plurality of alternating first and second time periods so as to form a plurality of first and second regions which alternate along the lengths of the nanowires.

5. *(Previously Presented)* A method as claimed in claim 1, wherein the nanowires are provided with a layer of a desired material in the dispersion.

6. *(Previously Presented)* A method as claimed in claim 5, wherein the desired material is provided by means of a sol-gel process.
7. *(Previously Presented)* A method as claimed in claim 5, wherein the material is silicon dioxide to which a luminescent coloring agent is bound.
8. *(Canceled)* A dispersion of nanowires of a semiconductor material in a dispersing agent obtainable by the method as claimed in claim 2.
9. *(Canceled)* A dispersion of nanowires of a semiconductor material in a dispersing agent, which nanowires are provided with a surface layer of a desired material.
10. *(Canceled)* A dispersion as claimed in claim 9, wherein the length of the wires lies in a range of between 0.3 and 1 μm .
11. *(Canceled)* A dispersion as claimed in claim 8, wherein the length of the wires is uniform within an error margin.
12. *(Previously Presented)* A method of manufacturing a device provided with nanowires on a substrate, in which method a dispersion of nanowires is provided on the substrate, wherein the dispersion as claimed in claim 7 is provided on the substrate.
13. *(Canceled)* An electronic device comprising a layer in which nanowires are dispersed, which nanowires have a predefined length distribution.